

Reg. No.

--	--	--	--	--	--	--	--	--	--	--	--	--

Question Paper Code : 52093

B.E./B.Tech. DEGREE EXAMINATION, MAY/JUNE 2016

Second Semester

Civil Engineering

PH 2161/PH 23/080040002 – ENGINEERING PHYSICS – II

(Common to all branches)

(Regulations 2008)

Time : Three Hours

Maximum : 100 Marks

Answer ALL questions.

PART – A (10 × 2 = 20 Marks)

1. Write down the expression for Fermi-Distribution function.
2. Give the expression for the carrier concentration in metals.
3. Compared with Germanium, Silicon is widely used to manufacture the elemental device. Why ?
4. Draw the graph for variation of Fermi level with temperature in p-type semiconductor.
5. What is the origin of magnetic moment ?
6. What are cryotron switches ?
7. Calculate the polarization produced in a dielectric medium of dielectric constant 6 when it is subjected to an electric field of 100 V/m. (Given $\epsilon_0 = 8.85 \times 10^{-12} \text{ Fm}^{-1}$)
8. Define dielectric breakdown and dielectric strength.
9. What is shape memory effect ?
10. What are the different crystalline forms of carbon ?

PART – B (5 × 16 = 80 marks)

11. (a) (i) State the postulates of classical free electron theory and derive an expression for thermal conductivity of metals. **(12)**
- (ii) A copper wire whose radius is 0.08 cm carries a steady current of 10 A. Calculate the current density of the wire and drift velocity of the free electron. ($n = 8.46 \times 10^{28}/\text{m}^3$). **(4)**

OR

- (b) (i) Derive an expression for the number of allowed states per unit volume of a solid. **(8)**
- (ii) Prove that the average energy of a free electron in metal is $3 E_{FO}/5$. **(8)**
12. (a) (i) Assuming the Fermi-Dirac distribution, derive an expression for the concentration of electrons per unit volume in the conduction band of an intrinsic semiconductor. **(12)**
- (ii) Find the intrinsic carrier concentration and Position of Fermi energy level I in Silicon with respect to the VB edge. Given $m_h = 0.92 m_0$; $m_e^* = 0.49 m_0$. $N_C = 2.21 \times 10^{25} /\text{m}^3$ and $N_V = 8.60 \times 10^{24}/\text{m}^3$ and $T = 300 \text{ K}$. **(4)**

OR

- (b) (i) With neat sketches, explain how Fermi level varies with impurity concentration and temperature in both p-type and n-type semiconductors. **(8)**
- (ii) What is Hall effect ? Describe an experimental arrangement to measure the Hall co-efficient. **(8)**
13. (a) Explain domain theory of ferromagnetism.

OR

- (b) Mention the difference between soft and hard superconductors. Describe principle and working of SQUID and Cryotron.

14. (a) Explain about :
- (i) Electronic Polarisation, Ionic Polarisation. (8)
 - (ii) Dielectric breakdown (8)

OR

- (b). Derive an expression for the internal field in a dielectric and hence obtain the Clausius-Mosatti equation. (16)

15. (a) (i) What are metallic glasses ? Explain how they are prepared by rapid quenching method. (2 + 6)
- (ii) List out the applications of metallic glasses. (4)
 - (iii) Explain what are the uses of shape memory alloys. (4)

OR

- (b) (i) What is fullerene ? (2)
- (ii) What are the applications of Carbon nanotubes ? (4)
 - (iii) Explain with necessary diagrams, the synthesis of nanomaterials using the following methods :
- (1) Chemical Vapour deposition (5)
 - (2) Sol-gel method. (5)